

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Thomas Osterheld et al.      Art Unit : Unknown  
 Serial No. : Unassigned      Examiner : Unknown  
 Filed : October 29, 2001  
 Title : POLISHING PAD HAVING A GROOVED PATTERN FOR USE IN  
 CHEMICAL MECHANICAL POLISHING

Box Patent Application  
 Commissioner for Patents  
 Washington, D.C. 20231

PRELIMINARY AMENDMENT

Prior to examination, please amend the application as follows:

In the specification:

Please replace the paragraph at page 1, line 6, with the following rewritten paragraph:

--This application is a continuation of pending U.S. Application Serial No. 09/441,633, filed November 16, 1999<sup>New ABN</sup> which is a divisional of U.S. Application Serial No. 09/003,315, filed January 6, 1998, now issued as U.S. Patent No. 5,984,769, which is continuation-in-part of U.S. Application Serial No. 08/856,948, filed May 15, 1997, now issued as U.S. Patent No. 5,921,855, the entire disclosures of which are incorporated herein by reference.--

In the claims:

Cancel claims 1-42.

Please add claims 43-54.

1 43. (New) A polishing pad for polishing a substrate in a chemical mechanical polishing system, comprising:

a layer having a thickness between about 0.06 and 0.12 inches, one side of the layer providing a polishing surface and having a plurality of substantially circular grooves formed therein, the grooves having a depth between about 0.02 and 0.05 inches.

24. (New) The polishing pad of claim 43, wherein the grooves have a depth of approximately 0.03 inches.

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